

Detection of Engineered Nanomaterials: Semiconductor Facilities and Consumer Devices

(Task Number: 425.040)

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Other Researchers:

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Objectives

- **Goal: To develop analytical methods for detecting and quantifying trace quantities nanomaterials relevant to the semiconductor industry in waste and recycled water, in lab air, and leached from packaged semiconductors**
- **Develop analytical methods for NM size distribution and quantification**
- **Develop capability to monitor NMs used in semiconducting manufacturing in air and water**
- **Assess NM release or leaching from electronic devices**

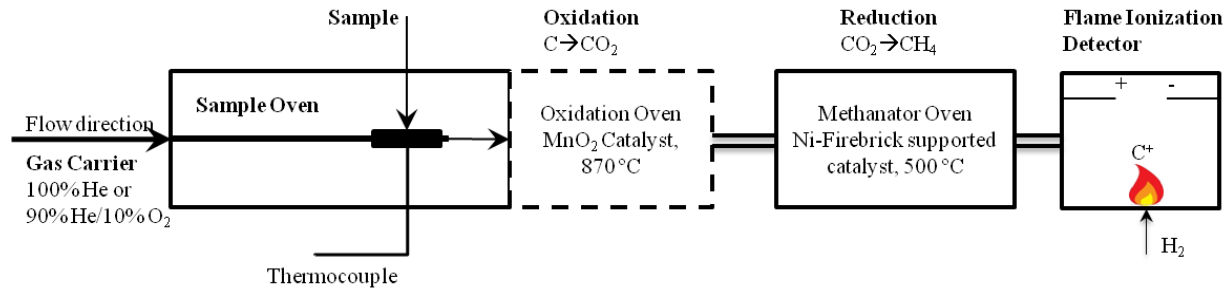
ESH Metrics and Impact

- 1. Provides analytical methods and SOPs using commercially available instruments for EHS monitoring of NMs in air and water**
- 1. Aid in ESH workplace exposure monitoring and assessment of remedial actions to reduce exposures, and in monitoring NMs after they leave fabrication facilities**
- 1. Aids in documenting nanomaterial fate over their life cycle**

Selected Nanomaterials

- As identified in the International Technology Roadmap for Semiconductors (ITRS):
 - CMP: silica, alumina, cerium oxide
 - Carbon nanotubes (MWCNT) in self-assembly or advanced packaging processes (alone and embedded in polymer matrices)
 - Exploring detection of nanographene platelettes because of their electronic properties

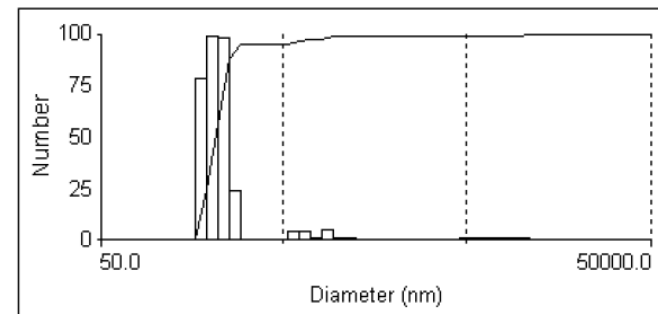
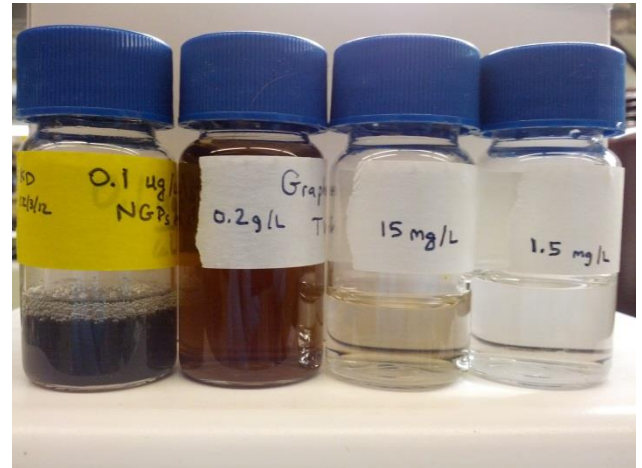
Thermal Optical Transmittance



- For MW or SW CNTs
- Uses unique thermal properties of CNTs
- Current detection limit is < 5 ug CNT
- Validated with over 15 different CNTs
- Next step: Use personal air sampler to collect and quantify CNTs (workplace exposure)

Graphene Nanoplateletes

- Highly conductive applications
- Graphene oxides
- 1-15 nm thick
- Analysis strategy:
 - Same as CNTs
 - Also using Raman
 - Preliminary findings indicate TOT analytical method will work for graphene



Metal Oxide Nanoparticle Detection

- **Single Particle ICP-MS**
- Uses instrumentation with modified data collection mode
- Sensitive to ppt levels
- Depending upon element can count NPs down to 5 nm
- Current focus has been spherical NMs, but works for nanowires

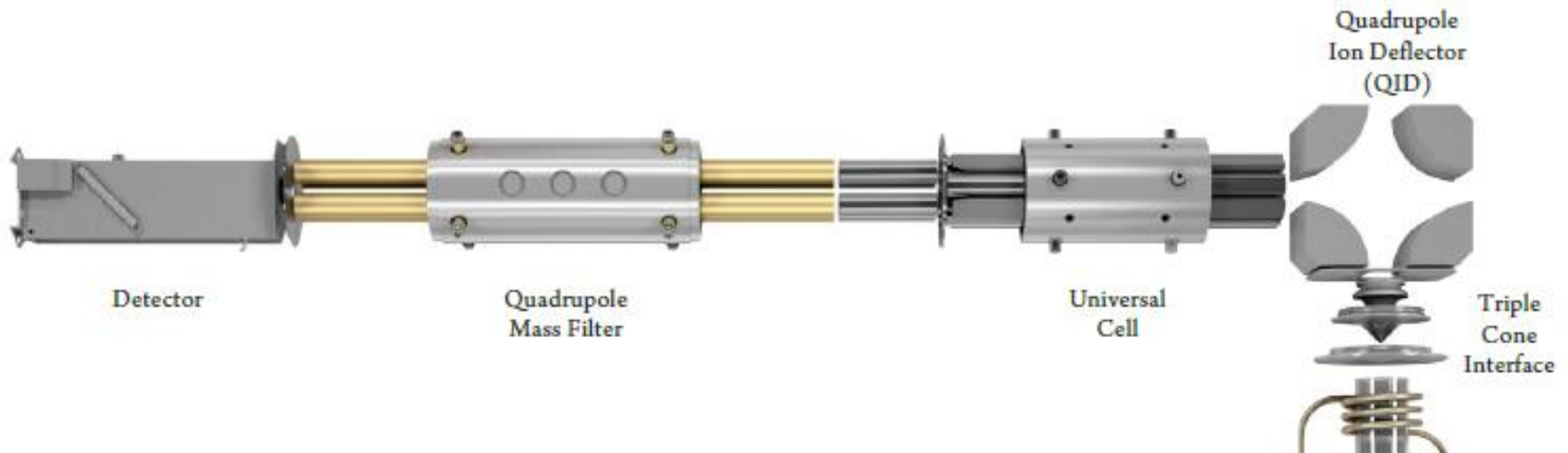


World-Wide SP-ICP-MS RoundRobin

- 21 labs across the globe
- Several Ag nanoparticles mailed out
- ASU and CSM facilities performed excellent – right on measured values
- A few labs showed poor results, but most showed consistent findings
- Validates reproducibility of SP-ICP-MS method

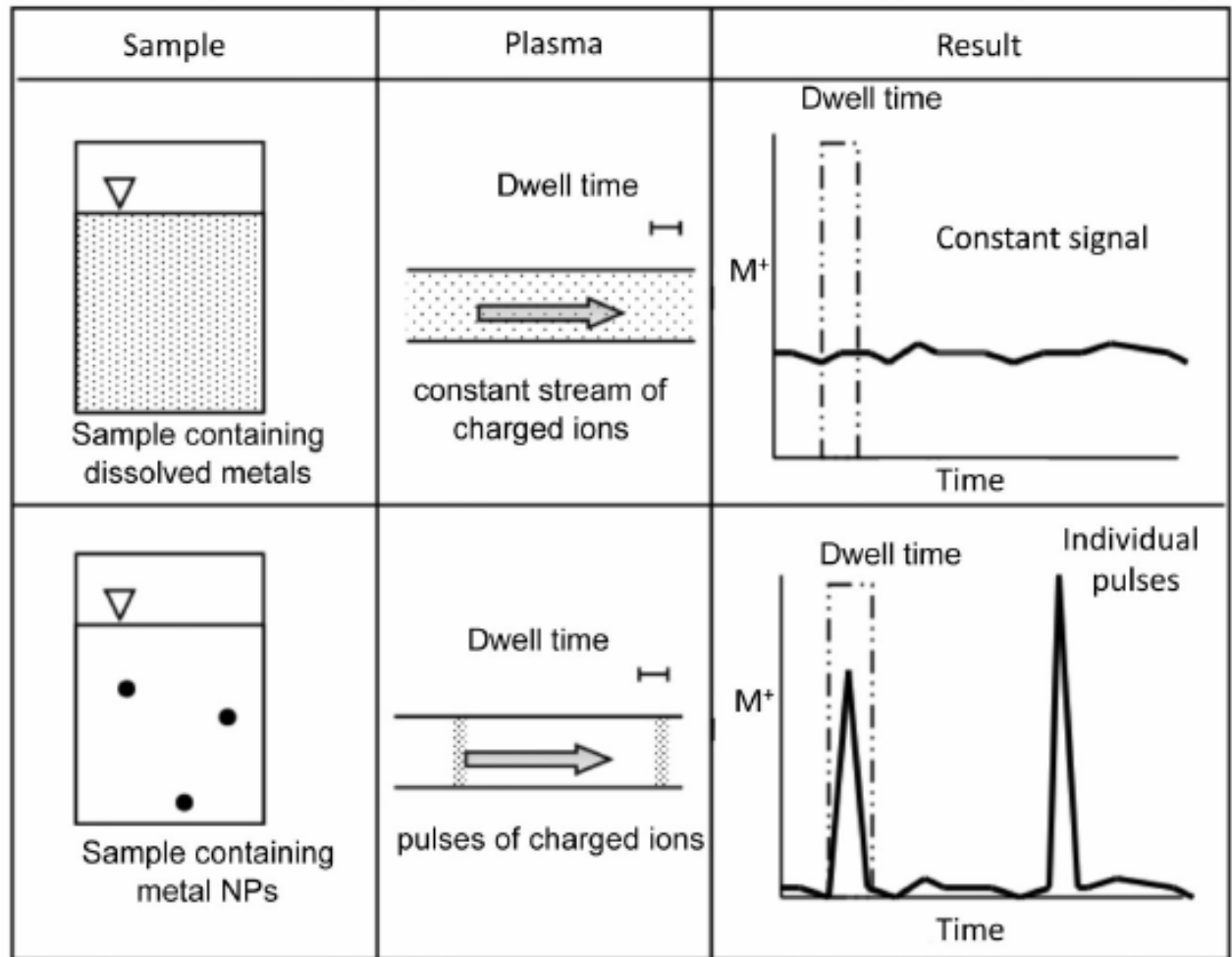
ICP-MS

- Element specific detection
- Isotopic analysis possible
- Detection limits at low part per trillion levels
- Analytical working range over 9 orders of magnitude.



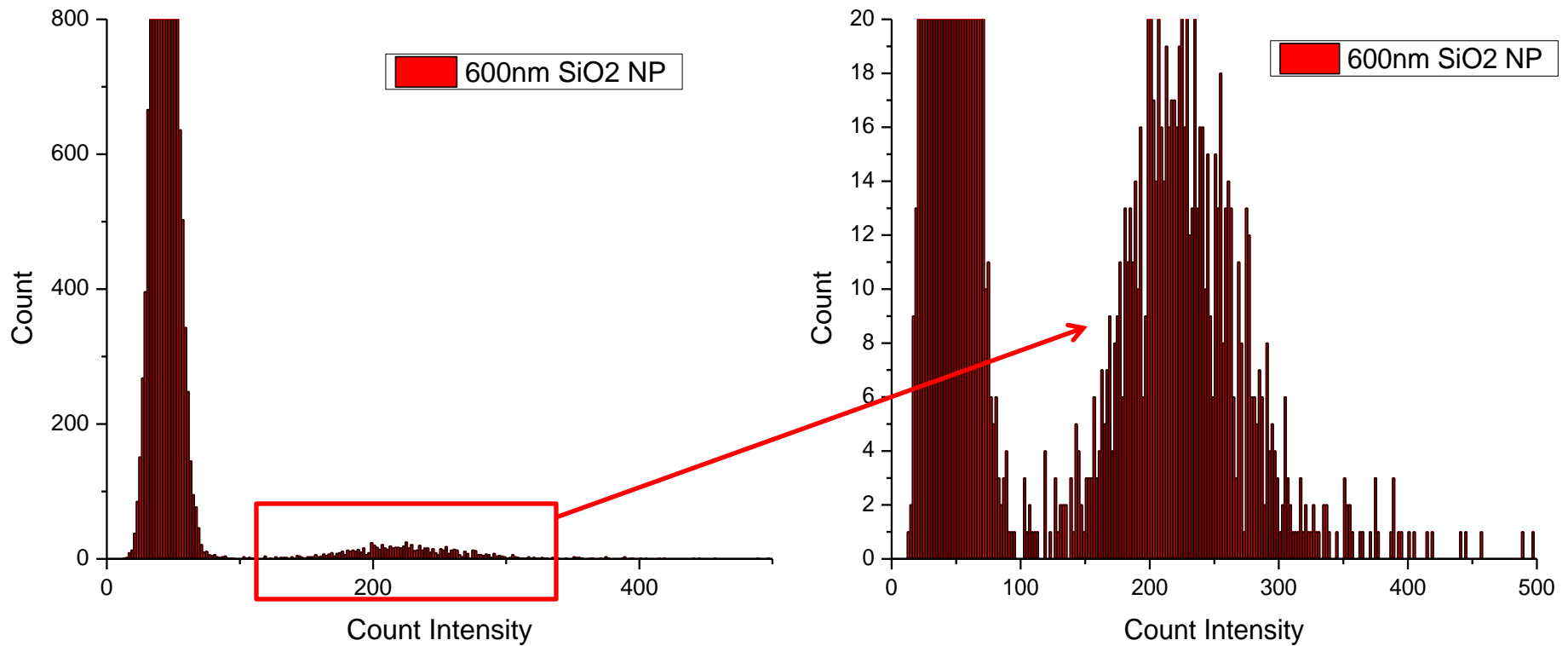
Principles of Single Particle ICP-MS

- Dissolved analyte gives a constant signal
- NP solution dilute: single nanoparticle in a single dwell time
- Assumption one pulse = one particle
- Number of pulses = number of nanoparticles



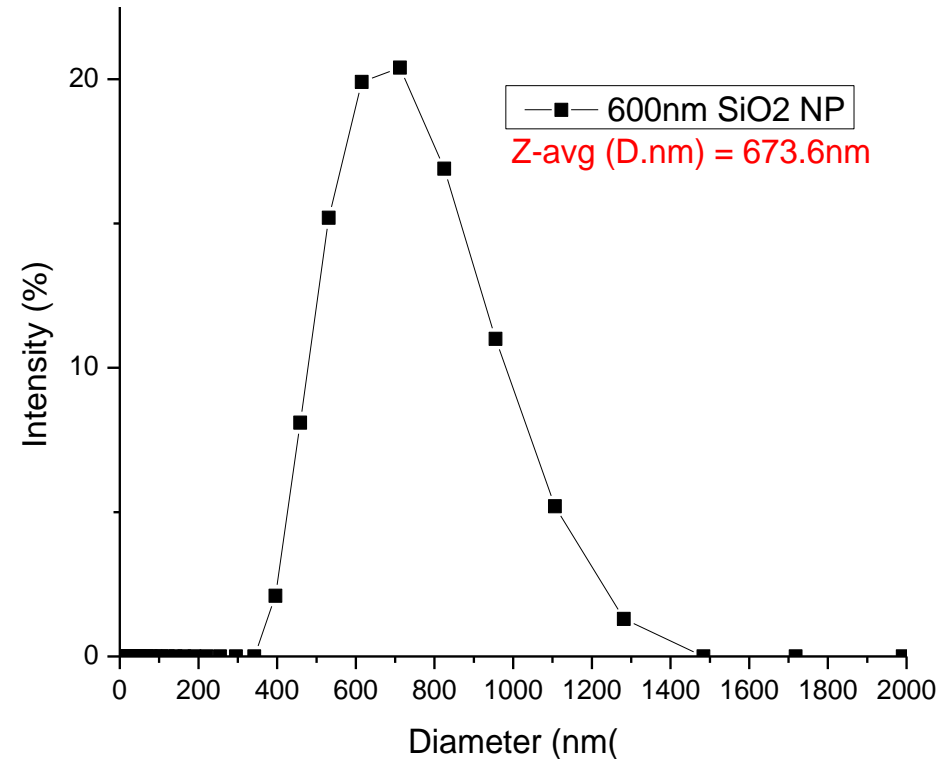
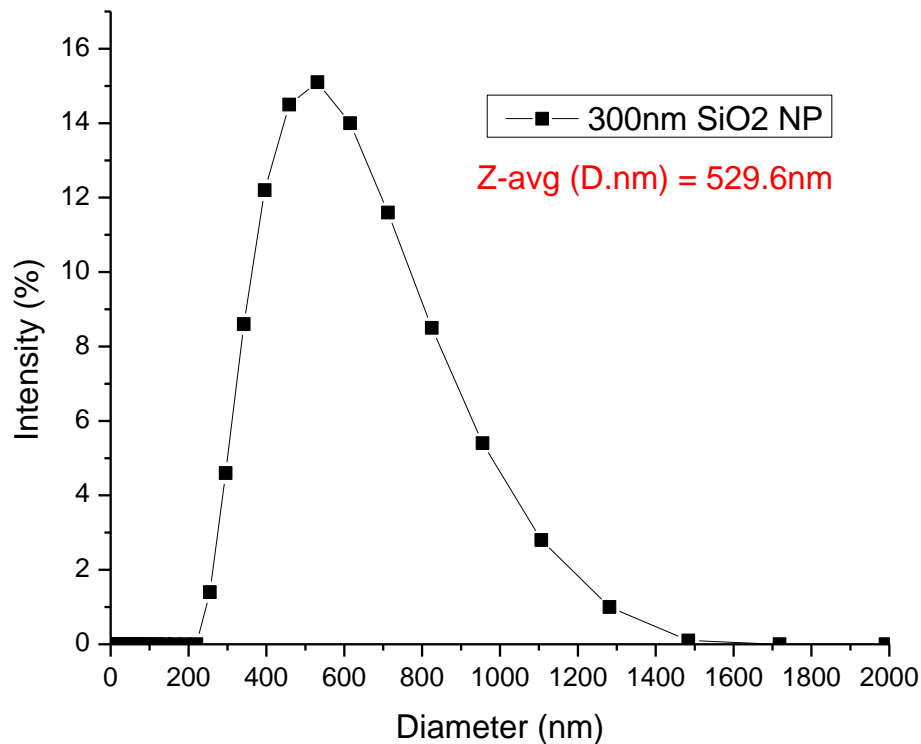
Mitrano, D.; Leshner, E.; Bednar, A. et al. *Environmental Toxicology and Chemistry*, 2012

Frequency count of 600nm Data

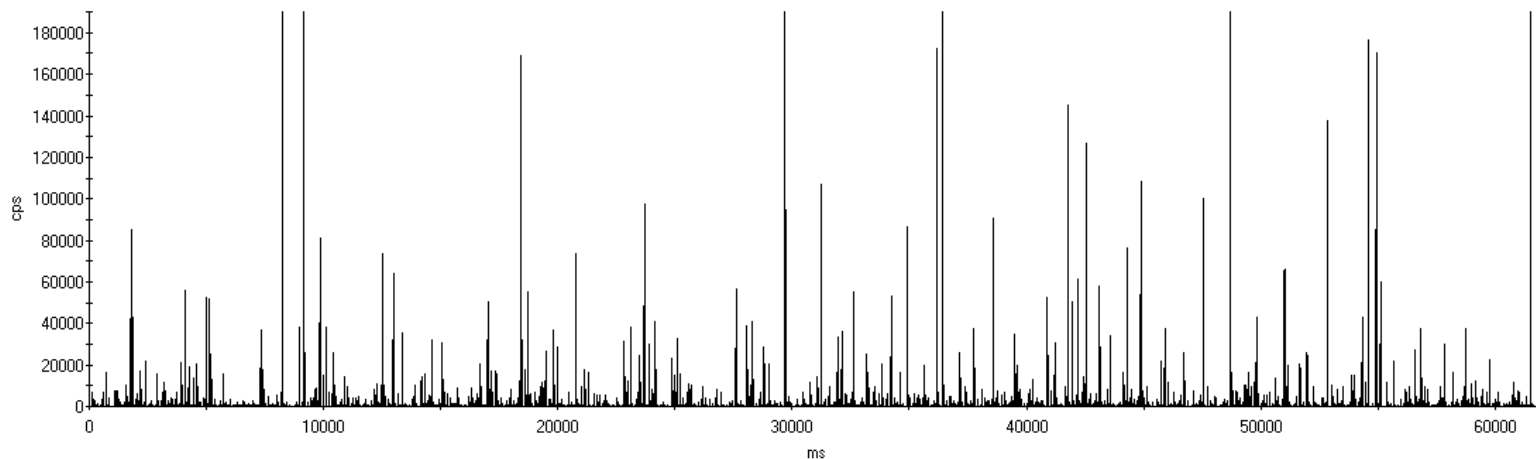
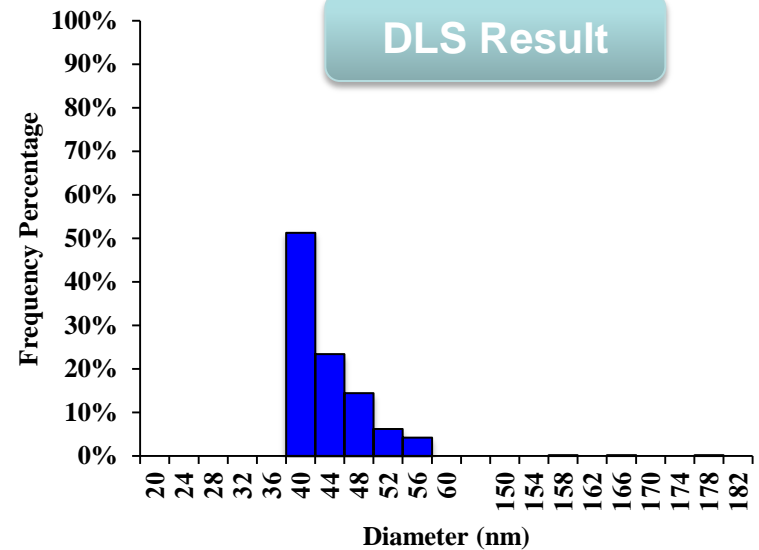
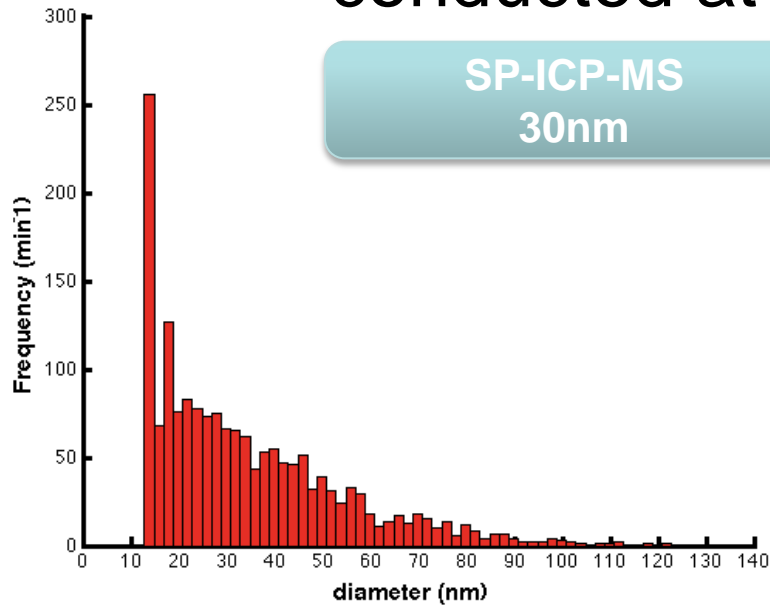


SiO₂ NP DLS

DLS showed particle sizes larger than those reported for 300 and 600 nm SiO₂ nanoparticles



SP-ICP-MS and DLS provide similar size distributions for CeO₂, but SP-ICP-MS is conducted at ppt concentrations

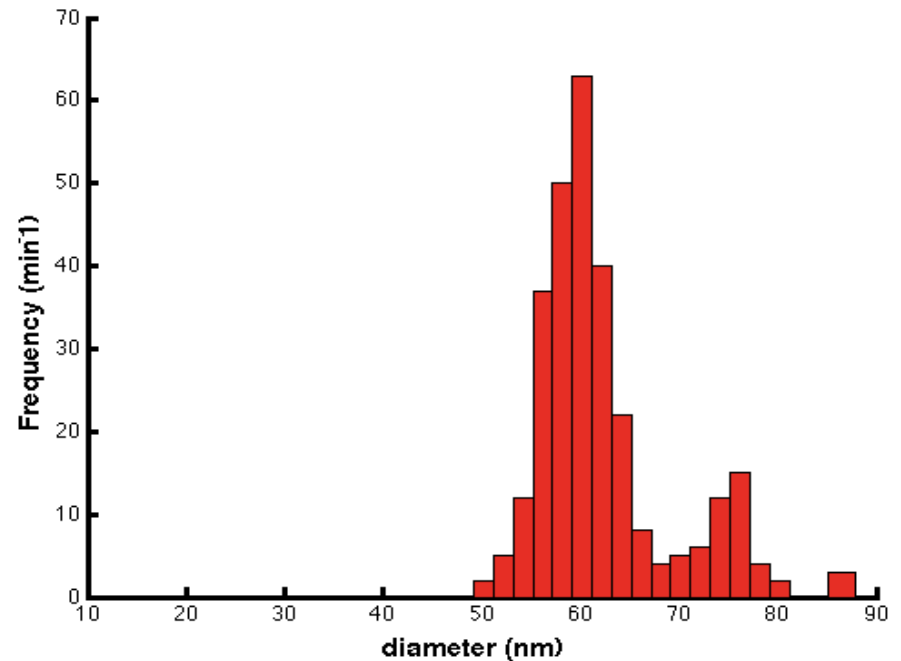
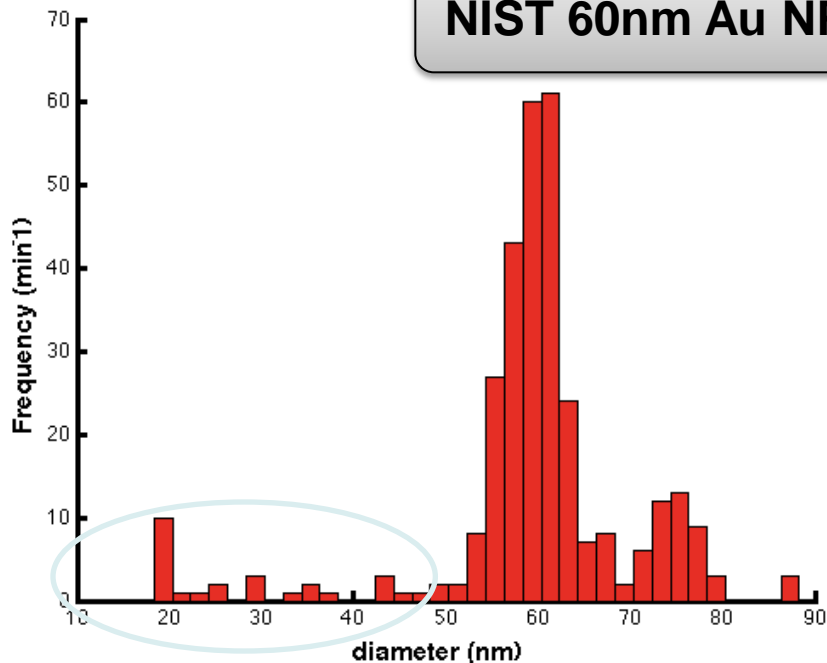


sp-ICP-MS Data Analysis

- Old method: statistical differentiation of signal from background using 4σ
- New method under development: K-Means Algorithm Method Application in particle signal processing in sp-ICP-MS Analysis

An example with Gold Nanoparticles

NIST 60nm Au NP



4 σ --- 316 particles out of 6164 pulses. 290 particles out of 6164 pulses.

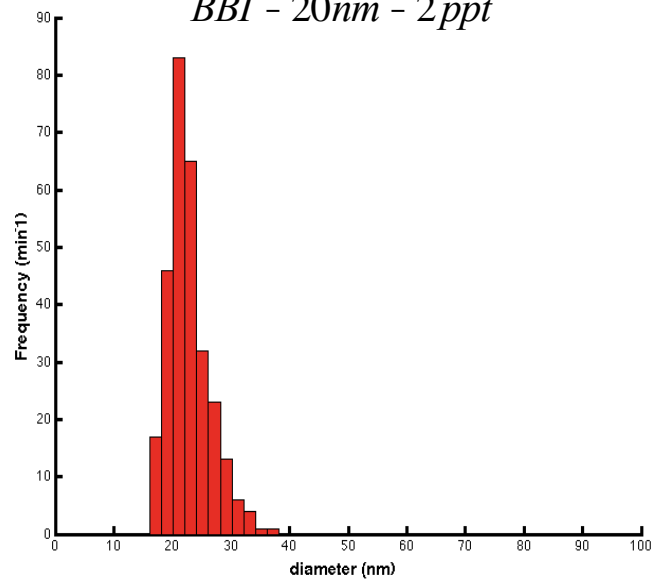
Conclusion: K-means offers a statistically robust data processing strategy for SP-ICP-MS

Using SP-ICP-MS to evaluate QA/QC on CMP fluids

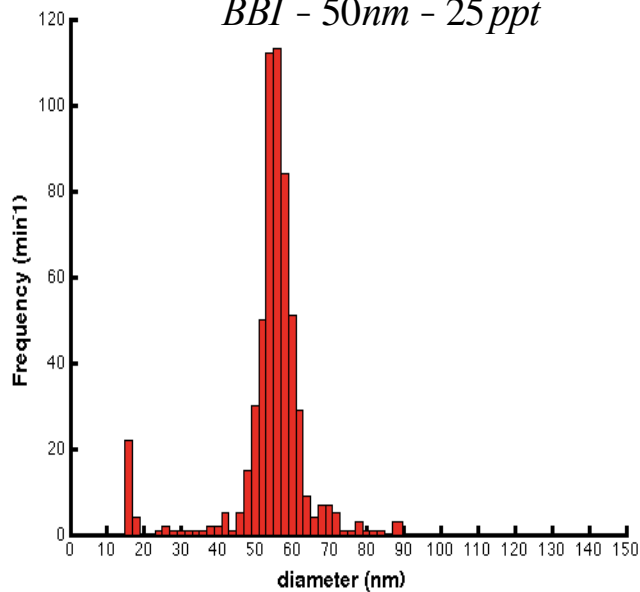
- Primary particle size: 250 nm Gold NP
- Impurity sizes: 20nm, 50nm, 70nm, 80nm, 100nm.
- Some parameters:
 - Dwell time: 10ms;
 - 4-sigma-principle differentiation
 - 5-nm bin size;
 - Optimal # concentration.
- Impurity percentage: 0.1%, 0.5%, 1%, 5% (mass-based).

Size distributions of some AuNPs

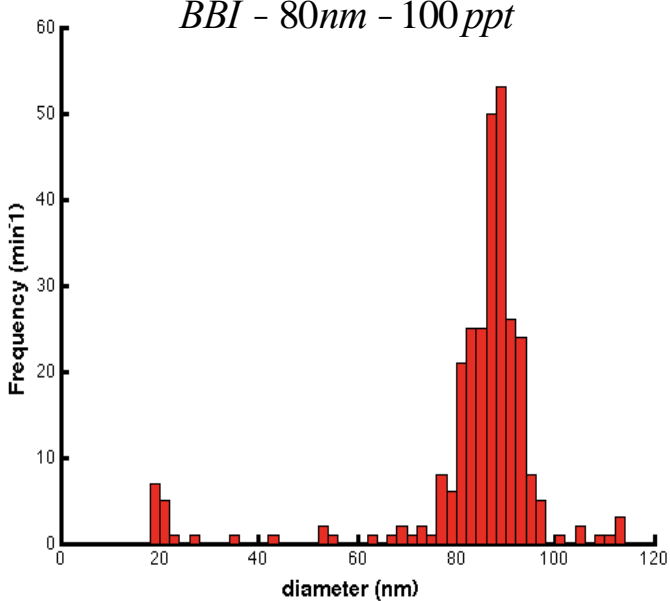
BBI - 20nm - 2 ppt



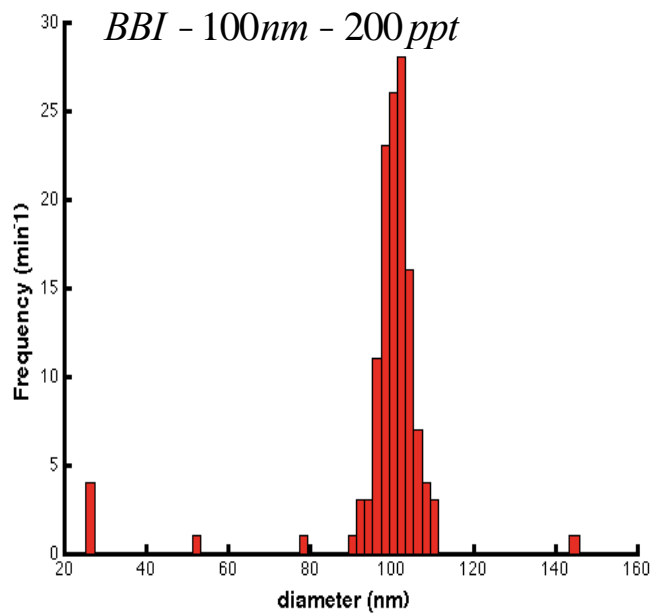
BBI - 50nm - 25 ppt



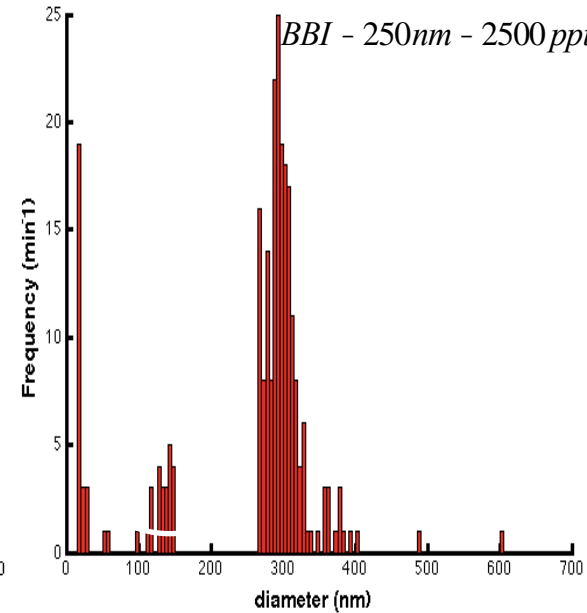
BBI - 80nm - 100 ppt



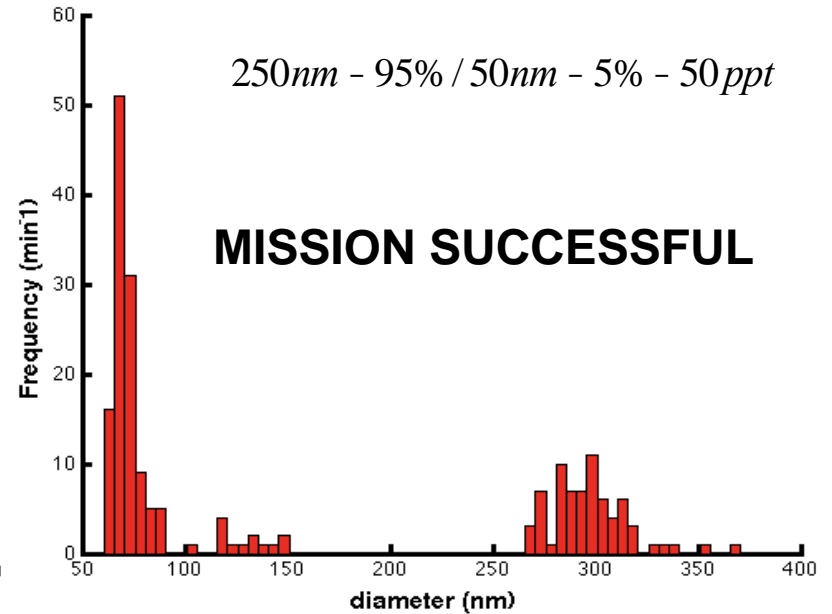
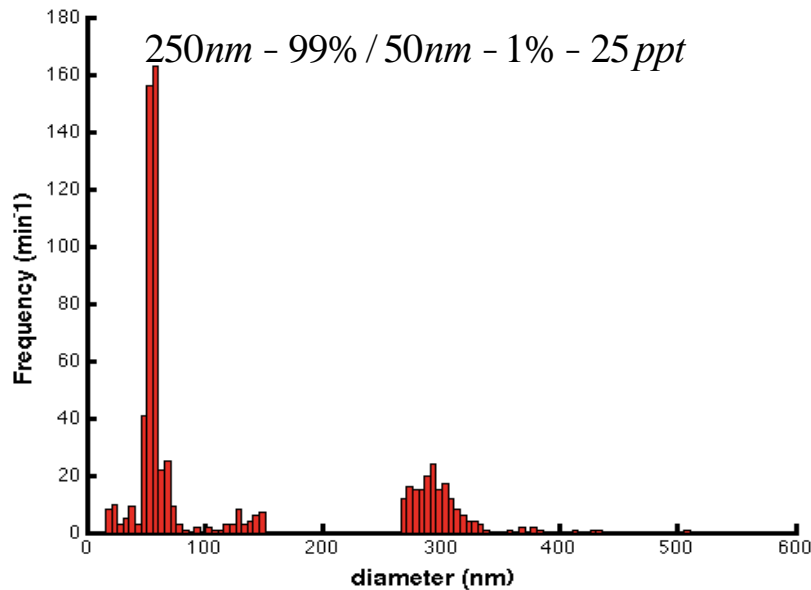
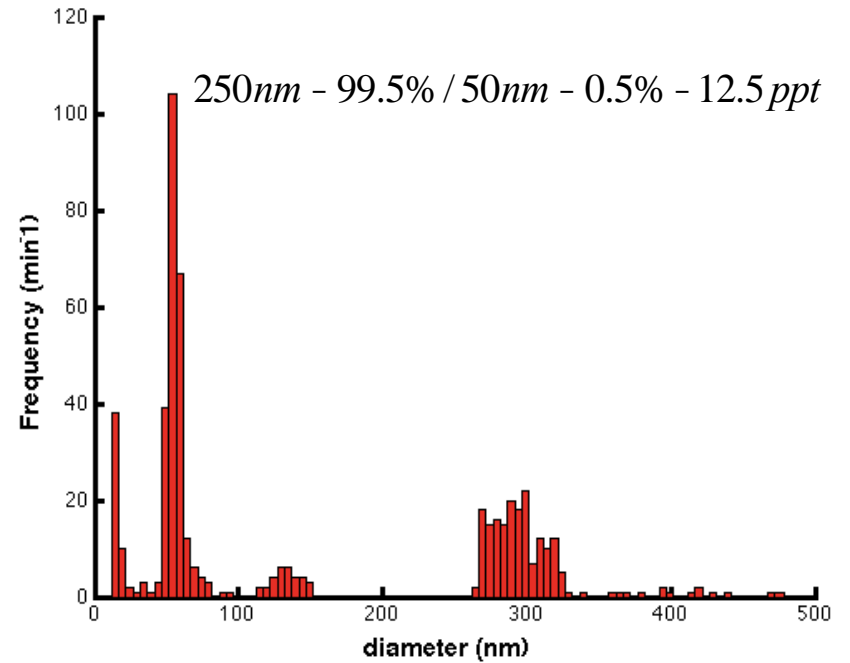
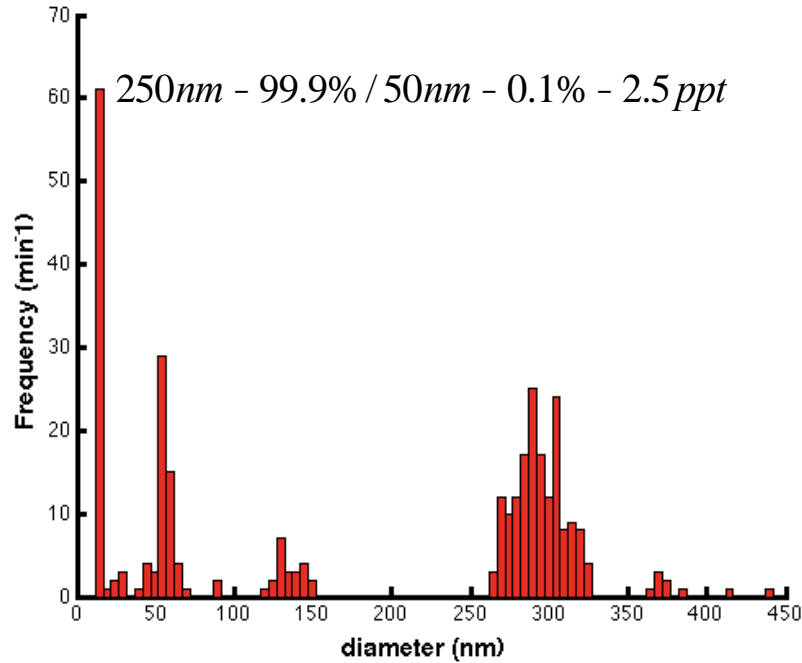
BBI - 100nm - 200 ppt



BBI - 250nm - 2500 ppt



250nm/50nm mixture



Industrial Interactions and Technology Transfer

- **Worked closely with IBM on understanding fate of CMP-based nanoparticles in on-site wastewater treatment system**
- **Collaborated in international sp-ICP-MS round robin**
- **Presented for a ERC/SRC monthly webcast**
- **Presented in 2012 at SRC annual meeting**
- **Organized and lead consortium of university researchers**

Future Plans

Next Year Plans

- **Improve size detection limit for SiO₂ by sp-ICP-MS and/or using ultrafiltration pretreatment**
- **Finalize CNT analytical SOP**
- **Demonstrate CNT exposure measurements (from air sampling)**
- **Finalize development of nanographene analytical technique**
- **Conduct jar tests to simulate CMP removal during industrial treatment & evaluate improvements to remove SiO₂ nanoparticles**

Long-Term Plans

- **Conduct on-site training for sp-ICP-MS**
- **Ability to quantify trace-level CMP-NMs in water leaving fabs and on personal air monitors**

Publications, Presentations, and Recognitions/Awards

- **Publications in process**
- **Presentation at TECHCON 2012**
- **Kyle Doudrick – 2013 Simon Karecki awardee**